

#3A

PTO/PCT Rec'd 27 DEC 2001

214810US-0PCT

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF :
YASUTAKA ITO ET AL : ATTN: APPLICATION DIVISION
SERIAL NO: 09/926,296 :
FILED: 09 October 2001 :
FOR: CERAMIC SUBSTRATE FOR :
A SEMICONDUCTOR-
PRODUCING/EXAMINING
DEVICE

PRELIMINARY AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

Prior to examination on the merits, please amend the above-identified application as follows.

IN THE CLAIMS

Please amend the claims as shown on the marked-up copy following this amendment

to read as follows.

4. (Amended) The ceramic substrate for a semiconductor-producing/examining
A1 device according to claim 1,
wherein said ceramic substrate is used in a temperature range of 100 to 700°C.

5. (Amended) The ceramic substrate for a semiconductor-producing/examining
device according to claim 1,